IEUVI Resist TWG meeting

Sunday February 25th, 8:00AM-12:30PM
San Jose Convention Center, Room 210C

8:00 start

Introduction - Paolo Gargini

Speaker	Title
• Toru Fujimori (Fujifilm)	Recent progress of CAR materials for EUV lithography
• Alex Robinson (U. Birmingham)	Progress in multi trigger resists
• Cliff Henderson (USF)	Non-traditional Approaches to Robust EUV Resist Materials Based on Molecular Resist, Crosslinking, and Depolymerization Schemes: An Update
• Takahiro Kozawa (U. Osaka)	Sensitization and reaction mechanisms of ZrO_2 nanoparticle resist
• Anindarupa Chunder (GlobalFoundries)	Enabling Next-gen EUV lithography: critical challenges in resists and process

10:00-10:15 coffee break

Speaker	Title
• Chris Mack (Lithoguru)	Reducing roughness in extreme ultraviolet lithography
• Alessandro Vaglio Pret (KLA-Tencor)	Comparative stochastic process variation bands for N5,N3 at EUV
• Greg Denbeaux (SUNY Poly)	Perspectives on resist stochastic issues
• Eishi Shiobara (EIDEC)	The recent status of resist outgas testing at EIDEC
• Sonia Castellanos Ortega (ARCNL)	LEEM research at ARCNL

12:30 finish